



PATENT

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

## INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Dear Sir:

Enclosed is form PTO-1449 listing twenty five references (25) that have been previously submitted by the Applicant and/or Examiner in a related Application (Serial Number 09/944,734 filed August 31, 2001) and additional copies are therefore not enclosed herewith in accordance with the provisions of 37 C.F.R. 1.98(d). This Information Disclosure Statement is being filed before the receipt of a first Office Action on the merits, and presumably no fee is required in accordance with 37 C.F.R. § 1.97(b)(3). If a first Office Action on the merits was mailed before the mailing date of this Statement, the Commissioner is authorized to charge the fee set forth in 37 C.F.R. § 1.17(p) to Deposit Account No. 11-1410.

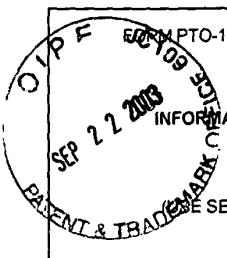
Respectfully submitted,

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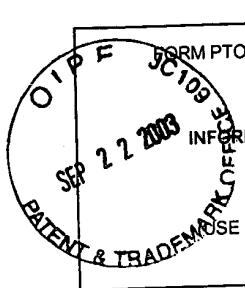
Dated: 11-13

 U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE INFORMATION DISCLOSURE STATEMENT BY APPLICANT (USE SEVERAL SHEETS IF NECESSARY)		ATTY. DOCKET NO. ASMEX.284DV1	APPLICATION NO. 10/626,217
		APPLICANT Pomarede, et al.	
		FILING DATE July 24, 2003	GROUP Unknown

U.S. PATENT DOCUMENTS							
EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE (IF APPROPRIATE)
1		2,394,930	2/12/46	McRae			
2		3,895,127	7/15/75	Comizzoli			
3		4,056,642	11/1/77	Saxena et al.			
4		4,292,343	9/29/81	Plaettner et al.			
5		4,343,830	8/10/82	Sarma et al.			
6		4,436,761	3/13/84	Hayashi et al.			
7		4,544,571	10/1/85	Miller			
8		4,645,683	2/24/87	Gourrier et al.			
9		4,766,006	8/23/88	Gaczi			
10		5,135,775	8/4/92	Foller et al.			
11		5,281,546	01/25/94	Possin et al.			
12		5,576,071	11/19/96	Sandhu			
13		5,587,205	12/24/96	Saito et al.			
14		5,780,115	7/14/98	Park et al.			
15		5,939,763	08/17/99	Hao et al.			
16		5,950,107	09/07/99	Huff et al.			
17		5,990,013	11/23/99	Berenguer et al.			
18		5,993,916	11/30/99	Zhao et al.			
19		6,107,192	08/22/00	Subrahmanyam et al.			
20		6,200,866	03/13/01	Ma et al.			

FOREIGN PATENT DOCUMENTS							TRANSLATION	
EXAMINER INITIAL		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
							YES	NO
21		JP 60 254621 A	16.12.85	Patent Abstracts of Japan				
22		JP 2000 160342 A	13.10.00	Patent Abstracts of Japan				
23		0 617 461 A2	03/16/94	EPO				

EXAMINER	DATE CONSIDERED
*EXAMINER: INITIAL IF CITATION CONSIDERED, WHETHER OR NOT CITATION IS IN CONFORMANCE WITH MPEP 609; DRAW LINE THROUGH CITATION IF NOT IN CONFORMANCE AND NOT CONSIDERED, INCLUDE COPY OF THIS FORM WITH NEXT COMMUNICATION TO APPLICANT.	



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EXAMINER INITIAL	OTHER DOCUMENTS (INCLUDING AUTHOR, TITLE, DATE, PERTINENT PAGES, ETC.)		
24	Kim, H. and R. Reif, <i>Thin Solid Films</i> , Vol. 289:192-198 (1996), "In-situ low-temperature (600°C) wafer surface cleaning by electron cyclotron resonance hydrogen plasma ...."		
25	Ramm J. and E. Beck, <i>Thin Solid Films</i> , Vol. 246:158-163 (1994), "Low temperature epitaxial growth by molecular beam epitaxy on hydrogen-plasma-cleaned silicon wafers."		

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